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		APPLICANT: <b>Christophe MALEVILLE et al.</b>	
		FILING DATE: <i>9/16/2003</i>	GROUP: <i>1746</i>

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>bs</i>	AA	5,158,100	10/1992	Tanaka et al.	134	105	
<i>f</i>	AB	5,232,870	8/1993	Ito et al.	437	173	
	AC	5,727,578	3/1998	Matthews	134	61	
	AD	5,776,296	7/1998	Matthews	156	345	
	AE	6,240,933 B1	6/2001	Bergman	134	1.3	
	AE	6,273,108 B1	8/2001	Bergman et al.	134	102.1	
	AF	2002/0050279 A1	5/2002	Bergman	134	3	
	AG	2002/0066464 A1	6/2002	Bergman	134	1	
<i>bd</i>	AH	2002/0157686 A1	10/2002	Bergman	134	1.3	

**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
<i>bd</i>	AI	EP 0 476 897 A2	3/1992	Europe			X	
<i>bs</i>	AJ	EP 0 731 495 A2		Europe			X	
	AK							

**OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)**

<i>bs</i>	AL	Kaneko et al., "Low Temperature Silicon Surface Cleaning by HF Etching/Ultraviolet Ozone Cleaning (HF/UVOC) Method (II)- in situ UVOC", Journal of Applied Physics, Vol. 28, No. 12, pp. 2425-2429 (1989)
	AM	
	AN	
	AO	

EXAMINER <i>S. Cole</i>	DATE CONSIDERED <i>8/11/04</i>
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.